

**INDUSTRY STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

SJ/T 11829.1-2022

**Plasma-enhanced chemical vapor deposition (PECVD)
equipment for crystalline silicon photovoltaic cells - Part 1:
Tubular PECVD equipment**

晶体硅光伏电池用等离子体增强化学气相淀积（PECVD）设备 第1部分：管式 PECVD 设备

(English Translation)

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What this standard covers

This standard specifies the terms and definitions, model designation, working environment, requirements, inspection methods, inspection rules, and packaging, marking, handling, transportation, and storage of tubular plasma-enhanced chemical vapor deposition (PECVD) equipment for crystalline silicon photovoltaic cells. This document applies to tubular PECVD equipment for crystalline silicon photovoltaic cells. The product is mainly used for the deposition and hydrogen passivation of anti-reflection film and passivation film on crystalline silicon photovoltaic cells.

Document data

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